



SDI Review Form 1.6

Journal Name:	International Research Journal of Pure and Applied Chemistry
Manuscript Number:	2013_IRJPAC_8704
Title of the Manuscript:	The role of the etching rates in three-dimensional simulations of the profile evolution
Type of the Article	

General guideline for Peer Review process:

This journal's peer review policy states that **NO** manuscript should be rejected only on the basis of '**lack of Novelty**', provided the manuscript is scientifically robust and technically sound.

To know the complete guideline for Peer Review process, reviewers are requested to visit this link:

(<http://www.sciencedomain.org/page.php?id=sdi-general-editorial-policy#Peer-Review-Guideline>)



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PART 1: Review Comments

	Reviewer's comment	Author's comment <i>(if agreed with reviewer, correct the manuscript and highlight that part in the manuscript. It is mandatory that authors should write his/her feedback here)</i>
<u>Compulsory</u> REVISION comments	The manuscript is literally a short version of the paper published previously on Sensor, and contains anything new to research community. The etch rate difference is well known and has fully studied. In fact, the figure 5 in the manuscript is incorrect. The transformation of etch shape is also known, and there are quite a few simulation software available.	All the Referee's comments were included in the revised manuscript. We would like to thank the Referee for help us to improve our manuscript. We agree with the Referee's opinion and remove Figure 5.
<u>Minor</u> REVISION comments		
<u>Optional/General</u> comments	For ethical issues where does Figures 4& 5 come from? the material in this manuscript has been previously published on journal Sensor.	We agree. We re-write some parts and put some different results.